

SHEET 1 of 1INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No.

NTI-030

Serial No.

10/040,055

Applicant

FALBO, James Kenneth

Filing Date

12/31/2001

Group

2825

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
HR	5,900,340	5/4/1999	Reich, et al.	430	22	3/3/1997
HR	5,920,487	7/6/1999	Reich, et al.	364	491	3/3/1997
HR	6,282,696 B1	8/28/2001	Garza, et al.	716	19	3/9/1999
HR	6,303,253 B1	10/16/2001	Lu	430	5	3/16/2000
HR	6,339,836 B1	1/15/2002	Eisenhofer, et al.	716	5	8/24/1998
HR	6,453,452 B1	9/17/2002	Chang, et al.	716	8	9/16/1998
HR	2002/0152449 A1	10/17/2002	Lin	716	17	4/13/2001
HR	2002/0152454 A1	10/17/2002	Cote, et al.	716	21	6/7/2002

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EXAMINER:

Heidi Rososhuk

Date Considered:

10/03/03

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INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No. NTI-030	Serial No. 10/040,055-29
	Applicant FALBO, James Kenneth	
	Filing Date 12/31/2001	Group 2825

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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
HR	4,895,780	1/23/1990	Nissan-Cohen, et al.	430	5	10/25/1988
HR	5,182,718	1/26/1993	Harafuji, et al.	364	490	3/29/1990
HR	5,208,124	5/4/1993	Sporon-Fiedler, et al.	430	5	3/19/1991
HR	5,340,700	8/23/1994	Chen, et al.	430	312	11/3/1993
HR	5,432,714	7/11/1995	Chung, et al.	364	525	9/2/1994
HR	5,533,148	7/2/1996	Sayah, et al.	382	240	9/30/1993
HR	5,538,815	7/23/1996	Oi, et al.	430	5	9/14/1993
HR	5,553,273	9/3/1996	Liebmann	395	500	4/17/1995
HR	5,553,274	9/3/1996	Liebmann	395	500	6/6/1995
HR	5,657,235	8/12/1997	Liebmann, et al.	364	474.24	5/3/1995
HR	5,663,017	9/2/1997	Schinella, et al.	430	5	6/7/1995
HR	5,663,893	9/2/1997	Wampler, et al.	364	491	5/3/1995
HR	5,682,323	10/28/1997	Pasch, et al.	364	491	3/6/1995
HR	5,705,301	1/6/1998	Garza, et al.	430	5	2/27/1996
HR	5,707,765	1/13/1998	Chen	430	5	5/28/1996
HR	5,740,068	4/14/1998	Liebmann, et al.	364	489	5/30/1996
HR	5,885,734	3/23/1999	Pierrat, et al.	430	5	8/15/1996
HR	6,009,250	12/28/1999	Ho, et al.	395	500.06	9/30/1997
HR	6,009,251	12/28/1999	Ho, et al.	395	500.06	9/30/1997
HR	6,011,911	1/4/2000	Ho, et al.	395	500.06	9/30/1997
HR	6,064,806	5/16/2000	Lakos, et al.	395	500.04	10/3/1997
HR	6,077,310	6/20/2000	Yamamoto, et al.	716	19	1/29/1999
HR	6,081,658	6/27/2000	Rieger, et al.	395	500.22	12/31/1997

EXAMINER: Hela KoneshuleDate Considered: 10/03/03

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INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No.	Serial No.
	NTI-030	10/040,055-1929
	Applicant	
	FALBO, James Kenneth	
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U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
HR	6,269,472 B1	7/31/2001	Garza, et al.	716	21	12/12/1997
HR	6,370,679 B1	4/9/2002	Chang, et al.	716	19	9/16/1998
HR	2002/0010904 A1	1/24/2002	Ayres	716	19	7/23/2001

EXAMINER: Hela Roshub

Date Considered: 10/03/03

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SHEET 3 of 5

INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No. NT1-030	Serial No. 10/040,055-29
	Applicant FALBO, James Kenneth	
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FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
HR	JP 3-80525	4/5/1991	JP			<input type="checkbox"/>	<input type="checkbox"/>
HR	WO 02/29491 A1	4/11/2002	WO			<input type="checkbox"/>	<input type="checkbox"/>
HR	GB 2,344,436 A	6/7/2000	GB			<input type="checkbox"/>	<input type="checkbox"/>
HR	WO 97/38381	10/16/1997	WO			<input type="checkbox"/>	<input type="checkbox"/>
HR	WO 99/14636 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
HR	WO 99/14637 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
HR	WO 99/14638 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>

EXAMINER: Helen KershnerDate Considered: 10/03/03

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Atty. Docket No.

NTI-030

Serial No.

10/040,055-29

Applicant

FALBO, James Kenneth

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITATION
HR	Lithas, "Lithas: Optical Proximity Correction Software" (2 pages).
HR	Microunity, "OPC Technology & Product Description", MicroUnity Systems Engineering, Inc., pp. 1-5.
HR	Rieger, M., et al., "Using Behavior Modeling for Proximity Correction", Precim Company, Portland, Oregon (6 pages).
HR	Trans Vector, "Now Better Quality Photomasks", Trans Vector Technologies, Inc., Camarillo, California (4 pages).
HR	Lin, B.J., "Methods to Print Optical Images at Low-k1 Factors", SPIE, Optical/Laser Microlithography III, Vol. 1264, pp. 2-13 (1990).
HR	Harafuji, K., et al., "A Novel Hierarchical Approach for Proximity Effect Correction in Electron Beam Lithography", IEEE, Vol. 12, No. 10, pp. 1508-1514, October 1993.
HR	Rieger, M., et al., "System for Lithography Proximity Compensation", Precim Company, Portland, Oregon, September 1993 (28 pages).
HR	Galan, G., et al., "Application of Alternating-Type Phase Shift Mask to Polysilicon Level for Random Logic Circuits", Jpn. J. Appl. Phys., Vol. 33, pp. 6779-6784 (1994).
HR	Garofalo, J., et al., "Automatic Proximity Correction for 0.35um I-Line Photolithography", IEEE, pp. 92-94 (1994).
HR	Pierrat, C., et al., "A Rule-Based Approach to E-Beam and Process-Induced Proximity Effect Correction for Phase-Shifting Mask Fabrication", SPIE, Vol. 2194, pp. 298-309 (1994).
HR	Henderson, R., et al., "Optical Proximity Effect Correction: An Emerging Technology", Microlithography World, pp. 6-12 (1994).
HR	Rieger, M., et al., "Customizing Proximity Correction for Process-Specific Objectives", SPIE, Vol. 2726, pp. 651-659 (1996).
HR	Yen, A., et al., "Optical Proximity Correction for 0.3um i-line Lithography", Microelectronic Engineering, Vol. 30, pp. 141-144, January 1996.
HR	Chen, J.F., et al., "Full-Chip Optical Proximity Correction with Depth of Focus Enhancement", Microlithography World (5 pages) (1997).

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SHEET 5 of 5

INFORMATION DISCLOSURE CITATION PTO-1449		Atty. Docket No. NTI-030 Applicant FALBO, James Kenneth Filing Date 12/31/2001	Serial No. 10/040,055-029 Group 2825
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)			
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HR	Tsujimoto, E., et al., "Hierarchical Mask Data Design System (PROPHET) for Aerial Image Simulation, Automatic Phase-Shifter Placement, and Subpeak Overlap Checking", SPIE, Vol. 3096, pp. 163-172 (1997).		
HR	Yamamoto, K., et al., "Hierarchical Processing of Levenson-Type Phase Shifter Generation", Jpn. J. Appl. Phys., Vol. 36, Part 1, No. 12B, pp. 7499-7503, December 1997.		
HR	Chuang, H., et al., "Practical Applications of 2-D Optical Proximity Corrections for Enhanced Performance of 0.25um Random Logic Devices", IEEE, pp. 18.7.1-18.7.4, December 1997.		
HR	Wong, A., et al., "Asymmetric Biasing for Subgrid Pattern Adjustment", SPIE, Vol. 4346, pp. 1-6 (2001).		

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